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Advances in X-Ray/EUV Optics and Components V

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Editors

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Contents

vii *Conference Committee*
ix *Introduction*

SESSION 1 X-RAY OPTICS AND APPLICATIONS

7802 02 **Development of a one-dimensional Wolter mirror for an advanced Kirkpatrick-Baez mirror** [7802-01]
S. Matsuyama, T. Wakioka, H. Mimura, T. Kimura, N. Kidani, Y. Sano, Osaka Univ. (Japan); Y. Nishino, Hokkaido Univ. (Japan); K. Tamasaku, M. Yabashi, T. Ishikawa, RIKEN/SPring-8 (Japan); K. Yamauchi, Osaka Univ. (Japan)

7802 03 **WSi_2/Si multilayer sectioning by reactive ion etching for multilayer Laue lens fabrication** [7802-31]
N. Bouet, Brookhaven National Lab. (United States); R. Conley, Brookhaven National Lab. (United States) and Argonne National Lab. (United States); J. Biancarosa, Brookhaven National Lab. (United States); R. Divan, A. T. Macrander, Argonne National Lab. (United States)

7802 04 **Compensation of fabrication errors in segmented x-ray optics** [7802-03]
M. Atanassova, W. Zhang, T. Saha, NASA Goddard Space Flight Ctr. (United States)

SESSION 2 VUV, SX OPTICS, AND APPLICATIONS

7802 06 **Beam splitting mirrors for miniature Fourier transform soft x-ray (FTXR) interferometer** [7802-05]
J. Wilcox, V. White, K. Shcheglov, R. Kowalczyk, Jet Propulsion Lab. (United States)

7802 07 **High-efficiency multilayer blazed gratings for EUV and soft x-rays: recent developments** [7802-06]
D. L. Voronov, Lawrence Berkeley National Lab. (United States); M. Ahn, Massachusetts Institute of Technology (United States); E. H. Anderson, R. Cambie, Lawrence Berkeley National Lab. (United States); C.-H. Chang, Massachusetts Institute of Technology (United States); L. I. Goray, Saint Petersburg Academic Univ. (Russian Federation) and Institute for Analytic Instrumentation (Russian Federation); E. M. Gullikson, Lawrence Berkeley National Lab. (United States); R. K. Heilmann, Massachusetts Institute of Technology (United States); F. Salmassi, Lawrence Berkeley National Lab. (United States); M. L. Schattenburg, Massachusetts Institute of Technology (United States); T. Warwick, V. Yashchuk, H. A. Padmore, Lawrence Berkeley National Lab. (United States)

7802 08 **Optical properties of carbon coatings for extreme-ultraviolet high-order laser harmonics** [7802-07]
S. Coraggia, F. Frassetto, L. Poletto, Istituto di Fotonica e Nanotecnologie-CNR (Italy); J. A. Aznarez, J. I. Larruquert, J. A. Mendez, Consejo Superior de Investigaciones Científicas (Spain); M. Negro, S. Stagira, C. Vozzi, Politecnico di Milano (Italy) and Istituto di Fotonica e Nanotecnologie-CNR (Italy)

7802 09 **Compact spectrometer for the analysis of high harmonics content of extreme-ultraviolet free-electron-laser radiation** [7802-08]
F. Frassetto, S. Coraggia, L. Poletto, Istituto di Fotonica e Nanotecnologie-CNR (Italy); N. Guerassimova, S. Dziarzhytski, E. Ploenjes, H. Weigelt, Deutsches Elektronen-Synchrotron (Germany)

SESSION 3 MULTILAYERS AND APPLICATIONS

7802 0A **DLC/Si multilayer mirrors for EUV radiation** [7802-09]
P. Gawlitza, S. Braun, A. Leson, Fraunhofer-Institut für Werkstoff- und Strahltechnik (Germany); W. Soer, M. Jak, Philips Research Nederland B.V. (Netherlands); V. Banine, ASML Netherlands B.V. (Netherlands)

7802 0B **In-situ stress measurements of sputtered multilayers** [7802-10]
Ch. Morawe, J.-Ch. Peffen, K. Friedrich, European Synchrotron Radiation Facility (France)

7802 0E **Stress analysis of Mo, MoSi$_2$, and Si mono-layer thin films and multilayers prepared by magnetron sputtering** [7802-13]
J. Zhu, Q. Huang, H. Li, F. Wang, X. Wang, Z. Wang, L. Chen, Tongji Univ. (China)

SESSION 4 MIRRORS, ZONE PLATES, AND APPLICATIONS

7802 0F **Investigation of aberrations of Kirkpatrick-Baez mirrors** [7802-14]
B. Ehlers, B. Verman, Rigaku Innovative Technologies (United States)

7802 0G **Platinum Kirkpatrik-Baez mirrors for a hard x-ray microfocusing system made by profile coating** [7802-15]
B. Shi, C. Liu, J. Qian, W. Liu, L. Assoufid, A. Khounsary, Argonne National Lab. (United States); R. Conley, Jr., Brookhaven National Lab. (United States); A. T. Macrander, Argonne National Lab. (United States)

7802 0H **Computer-controlled cylindrical polishing process for development of grazing incidence optics for the hard x-ray region** [7802-16]
G. S. Khan, M. Gubarev, C. Speegle, B. Ramsey, NASA Marshall Space Flight Ctr. (United States)

SESSION 5 X-RAY SOURCES AND DETECTORS

7802 0K **Robust liquid metal collector mirror for EUV and soft x-ray plasma sources** [7802-19]
K. Fahy, F. O'Reilly, E. Scally, P. Sheridan, Univ. College Dublin (Ireland)

SESSION 6 OPTICS AND BEAM COHERENCE

7802 0M **Micro-imaging performance of multilayers used as monochromators for coherent hard x-ray synchrotron radiation** [7802-22]
A. Rack, T. Weitkamp, European Synchrotron Radiation Facility (France); M. Riotte, T. Rack, Karlsruher Institut für Technologie (Germany); R. Dietsch, T. Holz, M. Krämer, AXO Dresden GmbH (Germany); F. Siewert, Helmholtz Zentrum Berlin (Germany); M. Meduna, Masaryk Univ. (Czech Republic); Ch. Morawe, P. Cloetens, E. Ziegler, European Synchrotron Radiation Facility (France)

7802 0O **Beam coherence and x-ray windows** [7802-32]
A. Khounsary, B. Lai, J. Qian, J. Maj, X. Huang, Argonne National Lab. (United States)

7802 0P **Analysis of mutual coherence of x-ray beam from rocking curves by perfect crystal** [7802-24]
H. Yamazaki, Japan Synchrotron Radiation Research Institute/SPring-8 (Japan); T. Ishikawa, RIKEN/SPring-8 (Japan)

POSTER SESSION

7802 0R **Modeling complex x-ray optical systems** [7802-02]
R. Schmitz, C. A. MacDonald, Univ. at Albany (United States)

7802 0S **EUV spectroscopic imaging observations of the first mission of Japanese small scientific satellites series** [7802-26]
K. Sakai, G. Murakami, G. Ogawa, T. Homma, I. Yoshikawa, The Univ. of Tokyo (Japan); K. Yoshioka, Rikkyo Univ. (Japan); M. Ueno, A. Yamazaki, K. Uemizu, Japan Aerospace Exploration Agency (Japan); M. Kagitani, F. Tsuchiya, N. Terada, Tohoku Univ. (Japan)

7802 0T **Compact extreme ultraviolet source by use of a discharge-produced potassium plasma for surface morphology application** [7802-27]
H. Terauchi, M. Yamaguchi, K. Kikuchi, T. Otsuka, Utsunomiya Univ. (Japan); T. Higashiguchi, N. Yugami, Utsunomiya Univ. (Japan) and Japan Science and Technology Agency (Japan); T. Yatagai, Utsunomiya Univ. (Japan); P. Dunne, G. O'Sullivan, Univ. College Dublin (Ireland)

7802 0U **Improved synchrotron performance from indium antimonide crystals** [7802-28]
B. Yates, Y. Hu, V. Nagarkal, Canadian Light Source Inc. (Canada)

7802 0W **Ultrasound artificial anisotropy of crystals in x-ray frequency range** [7802-30]
V. P. Mkrtchyan, L. G. Gasparyan, M. K. Balyan, Yerevan State Univ. (Armenia)

Author Index

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1 X-ray Optics and Applications
Shunji Goto, Japan Synchrotron Radiation Research Institute (Japan)
Hans M. Hertz, Royal Institute of Technology (Sweden)

2 VUV, SX Optics, and Applications
Ali M. Khounsary, Argonne National Laboratory (United States)
Carolyn A. MacDonald, University at Albany (United States)

3 Multilayers and Applications
Kazuto Yamauchi, Osaka University (Japan)
Raymond Conley, Jr., Brookhaven National Laboratory (United States)

4 Mirrors, Zone Plates, and Applications
Christian Morawe, European Synchrotron Radiation Facility (France)
Horst Schulte-Schrepping, Deutsches Elektronen-Synchrotron (Germany)

5 X-ray Sources and Detectors
Peter Gawlitza, Fraunhofer-Institut für Werkstoff- und Strahltechnik (Germany)
Lucia Alianelli, Diamond Light Source Ltd. (United Kingdom)

6 Optics and Beam Coherence
Brian W. Yates, Canadian Light Source Inc. (Canada)

Introduction

This volume contains papers presented at the conference on "Advances in X-Ray/EUV Optics and Components V", held in San Diego, California, USA, on 2–3, August 2010, as part of the SPIE 2010 International Symposium on Optics + Photonics.

The conference was in six sessions covering "X-ray Optics and Applications," "VUV, SX Optics, and Applications," "Multilayers and Applications," "Mirrors, Zone Plates, and Applications," "X-ray Sources and Detectors," and "Optics and Beam Coherence." It was complemented by a poster session and by other conferences in the X-Ray, Gamma-Ray, and Particle Technologies program track, i.e. on metrology and adaptive x-ray optics.

This conference focused on technological developments in X-ray/EUV optics in astronomy, laser physics, and synchrotron beamline design. Accordingly, the applications covered the spectral range from vacuum ultra violet (VUV) to hard x-rays. Topics related to metrology were presented in the above-mentioned metrology conferences.

This was a very fruitful conference and we would like to thank the authors, speakers, session chairs, program committee members, conference participants, and SPIE staff for their help in making it a success.

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Christian Morawe